

Virtual substrates for wide bandgap $\text{Al}_y\text{X}_{1-y}\text{N}$ growth

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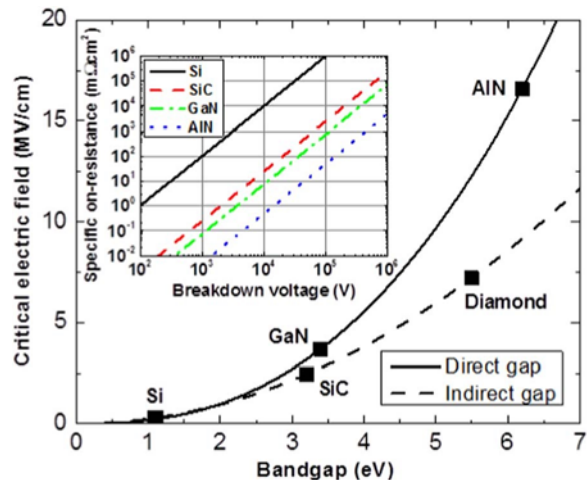
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Increased electrification drives the need for power electronics

Why AlGaN?



- Larger band gaps (ultra-wide!) enable larger electric fields
 - p- and n-dopable
 - high mobility and stability
 - Mature growth processes

100%
All Primary
Energy

40%

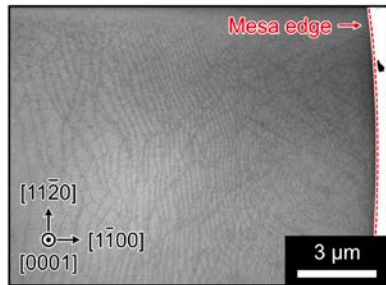
Electricity is 40% of total primary energy consumption, expected to grow

30%

30% of all electrical energy passes through power electronics today, can reach 80% next decade

Significant energy savings with small efficiency improvements

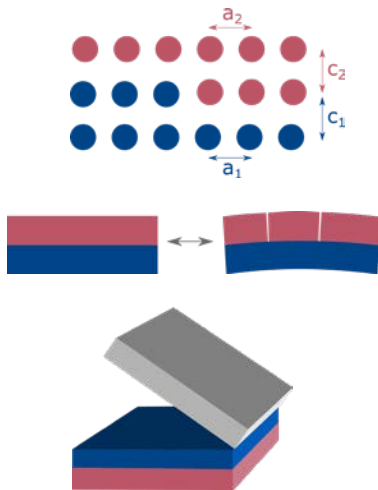
The effect of the substrate



Main deployment barrier: lattice mismatch causing layer cracking and dislocations, impacting optical and electrical properties

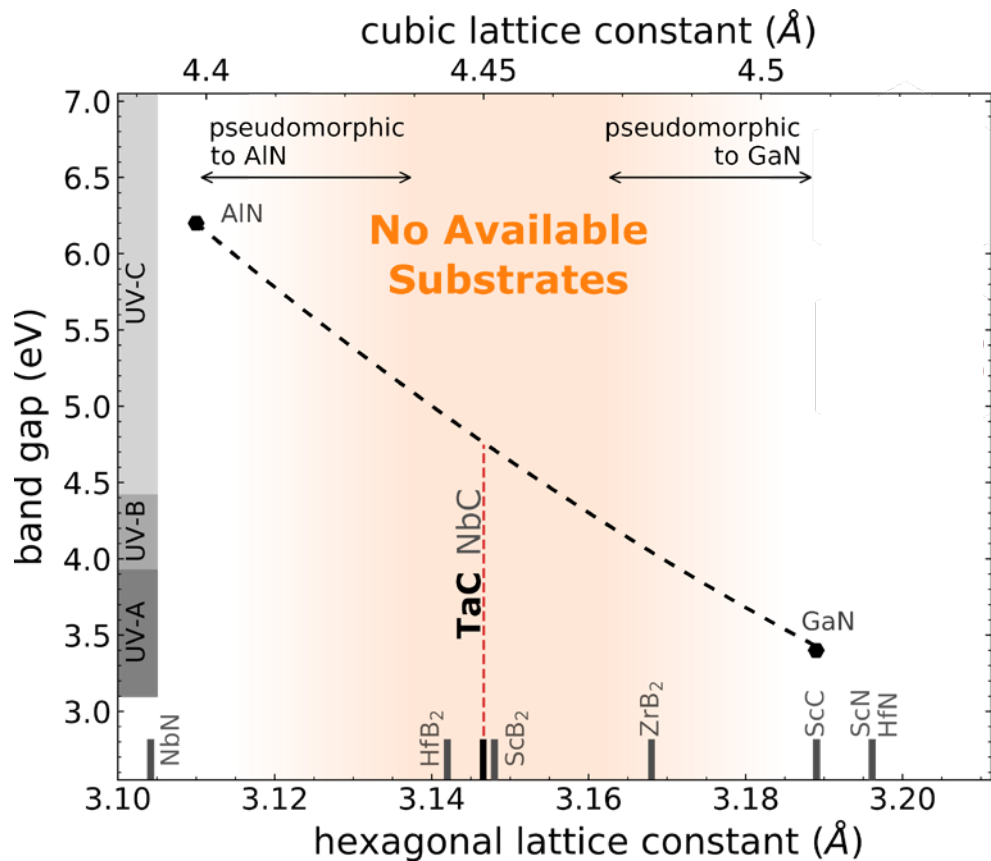
< *Dislocations in AlGaN on AlN device – Kumabe et al, IEEE Trans. on Electronic Devices 2024*

Properties of an ideal substrate



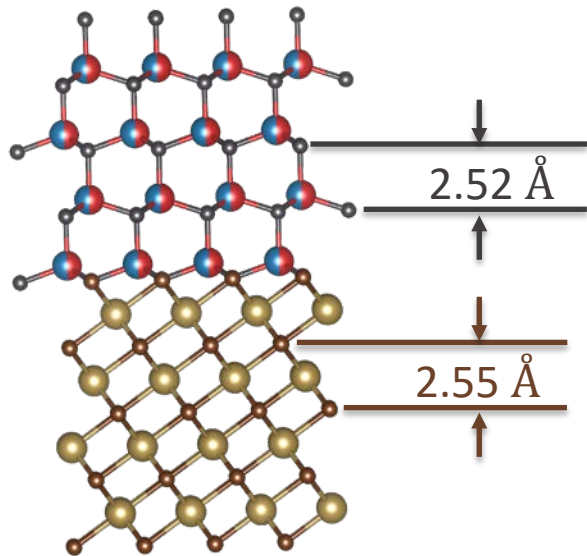
- Lattice matched – both in-plane (atomic registry) and out-of-plane (step height registry)
- Thermal-expansion matched – growth temperature and cooling
- Scalability – low-cost manufacturing techniques
- Device compatibility – electrically conductive with good thermal conductivity for vertical devices
- Bonus – chemically/optically dissimilar for substrate removal

Transition metal carbides are lattice matched to AlGaN

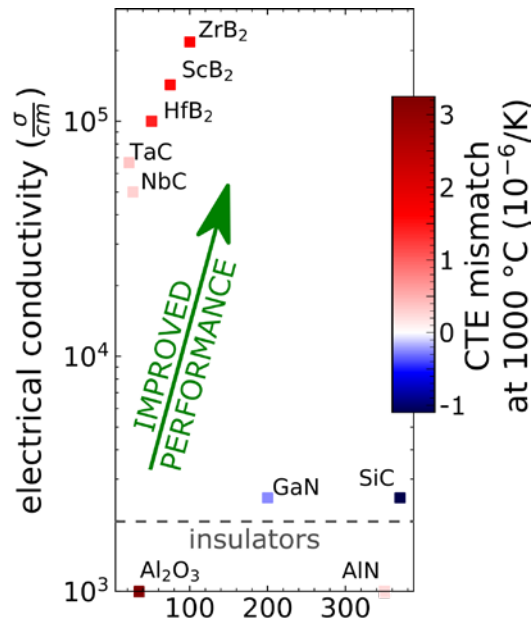


- (111) TaC is lattice matched to $\text{Al}_{0.45}\text{Ga}_{0.55}\text{N}$ (0001)
- Potential tunability via process parameters and alloying!

Transition metal carbides are lattice matched to AlGaN

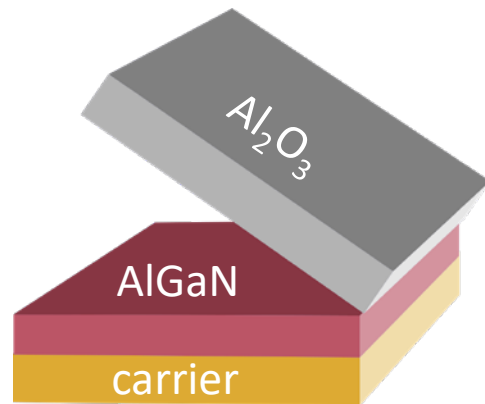


TaC (111) is lattice matched to $\text{Al}_{0.55}\text{Ga}_{0.45}\text{N}$ (0001)



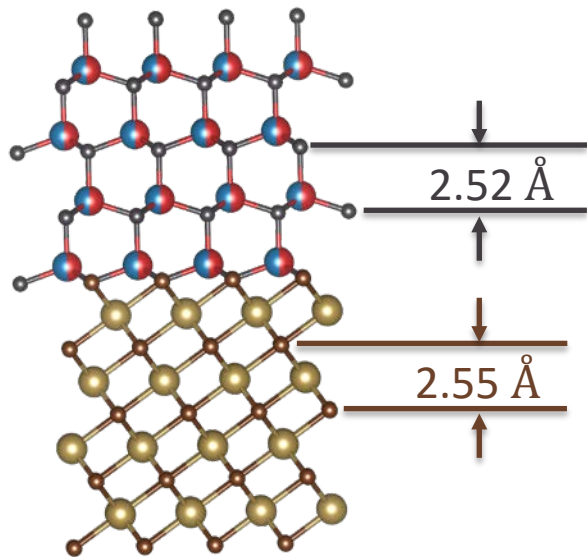
Thermal Conductivity ($\frac{W}{m-K}$)

Conductive with compatible CTE

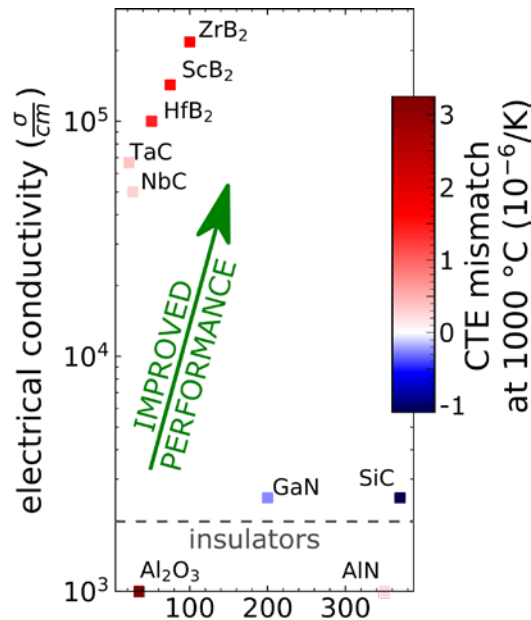


Chemically dissimilar – potential for substrate removal

Transition metal carbides are lattice matched to AlGaN

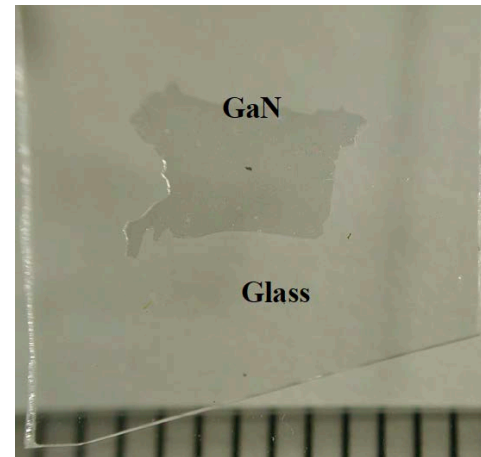


TaC (111) is lattice matched to $\text{Al}_{0.55}\text{Ga}_{0.45}\text{N}$ (0001)



Thermal Conductivity ($\frac{W}{m \cdot K}$)

Conductive with compatible CTE



Freestanding GaN removed from ZrB_2

Hiroshi Amano et. al., Proc. SPIE 2003

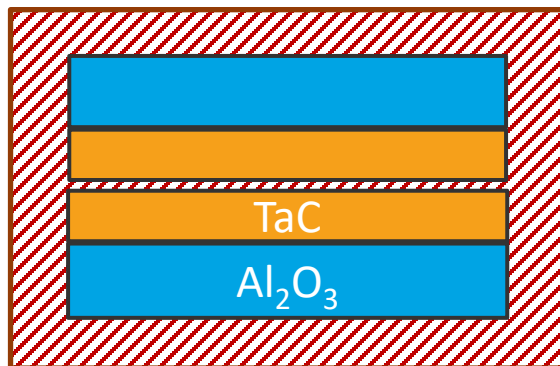
Approach



Step 1: sputter deposition



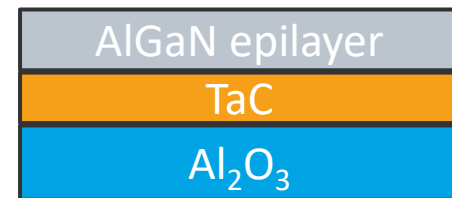
Grow epitaxial TaC



Step 2: annealing $> 1400\text{ }^\circ\text{C}$



Improve crystal quality

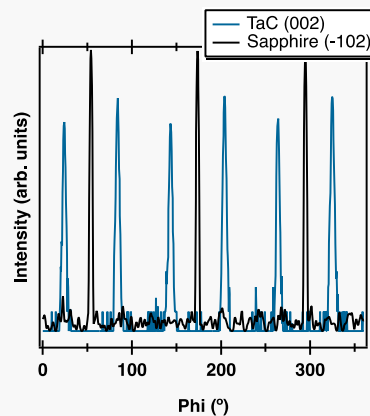
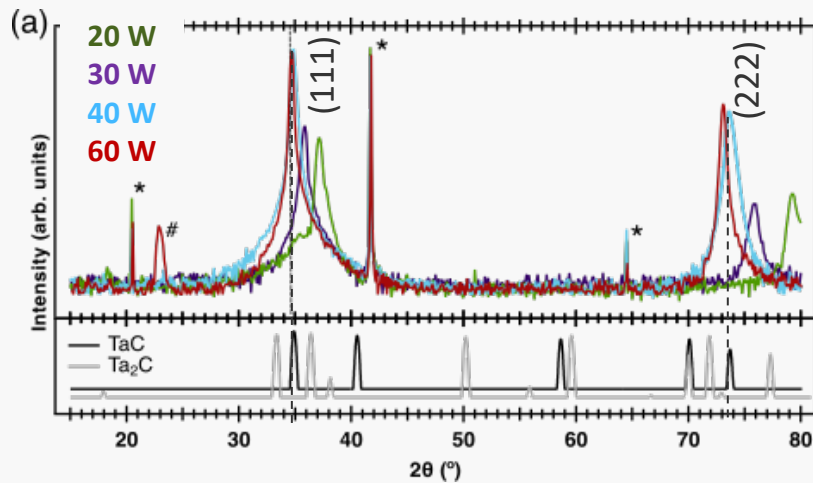


Step 3: epilayer growth

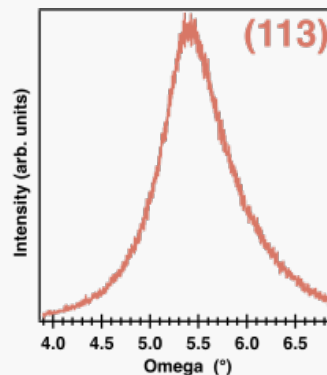
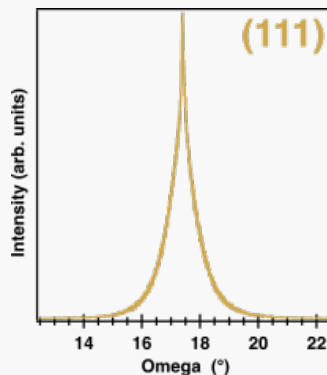
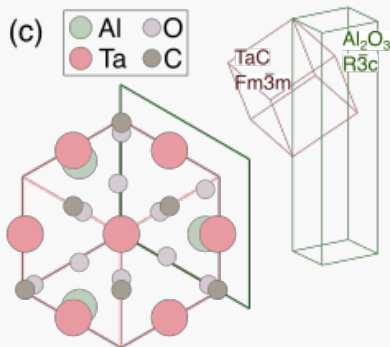


Grow LM AlGaIn by MBE

Sputter growth of TaC thin films on sapphire



- Crystallinity improves with TaC target power
- Twins with slight site preference

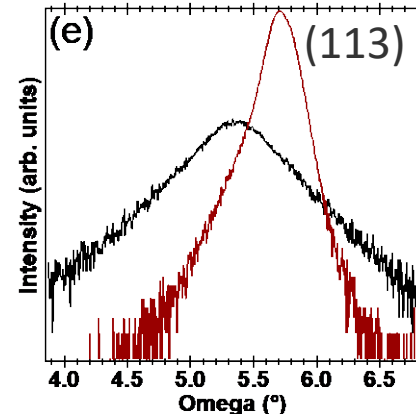
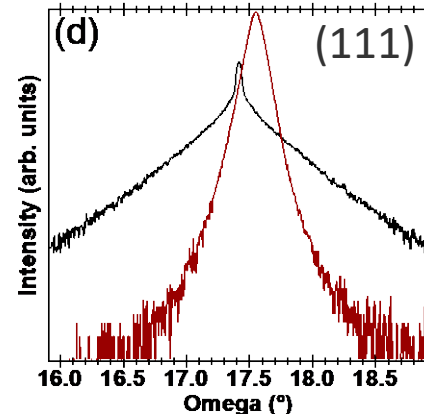
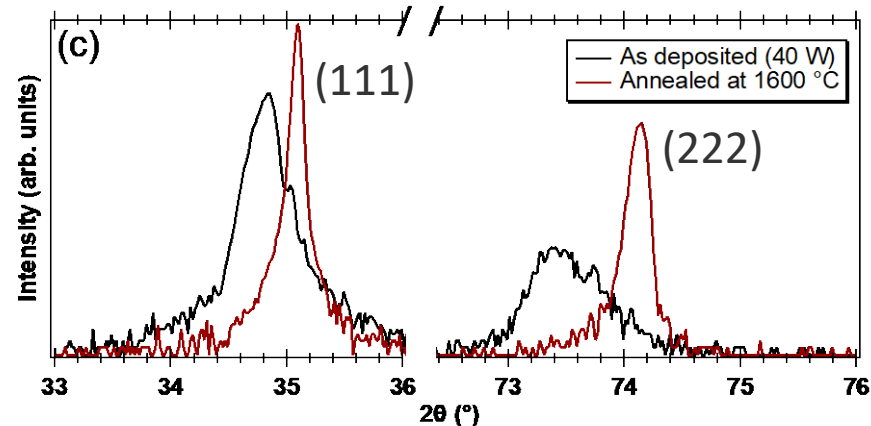
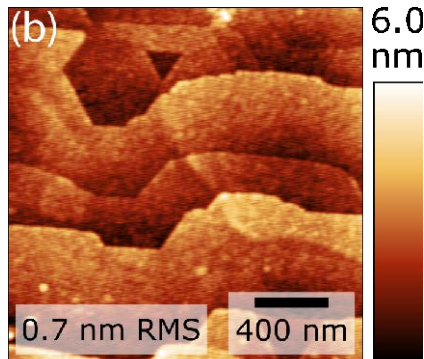
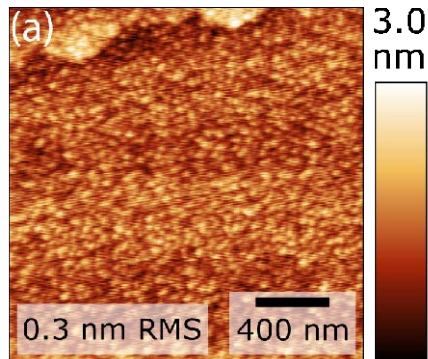


- In-plane relationship $\{11\bar{2}\}_{\text{TaC}} \parallel (10\bar{1}0)_{\text{Al}_2\text{O}_3}$
- Verify TaC presence and track structural quality via in plane (113) peak

Engineering substrate layers



Annealing at 1600 °C in a face-to-face configuration results in step-and-terrace surfaces and significantly improved crystallinity as measured by XRD



AFM of surface as deposited and after annealing

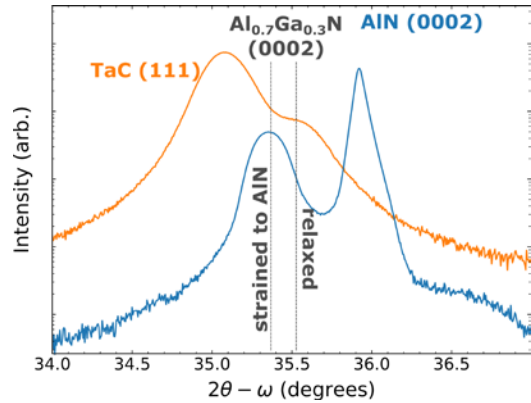
X-ray diffraction and rocking curves
before and **after** annealing

Growth of AlGaN on TaC and analysis of interface

AlGaN

TaC

Sapphire



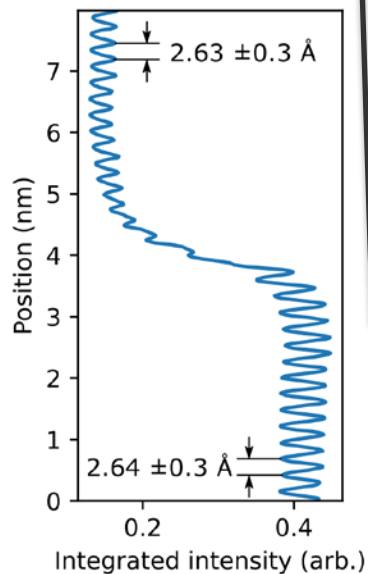
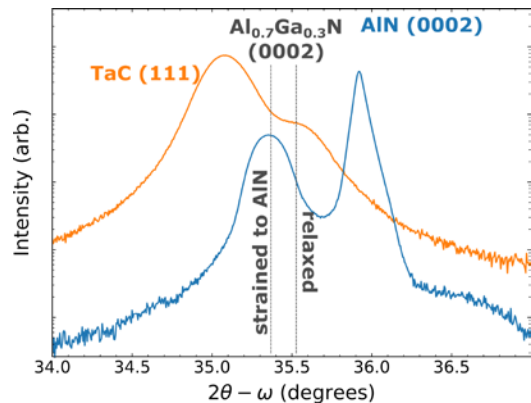
Growth of AlGaN on TaC and analysis of interface

AlGaN

TaC

100.0 kV SuperScan
10 nm

HAADF in collaboration with CNMS



100.0 kV SuperScan
1 nm

- Contrast variation indicates inhomogeneous composition directly above the interface
- Some defects and stacking irregularity are observed
- However – fairly abrupt interface!

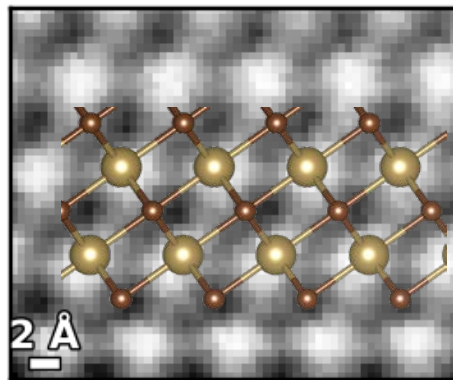
Clear metal polar wurtzite observed by atomic resolution STEM imaging

Metal and nitrogen positions are clearly visible by annular dark field

TaC rock salt structure clearly observed

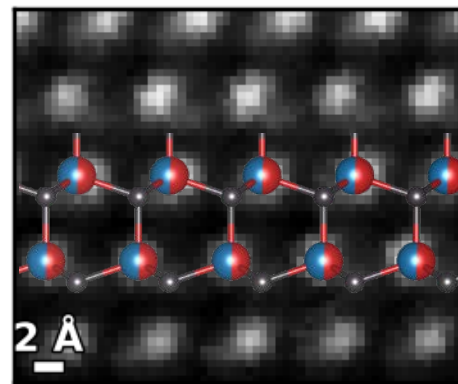


TaC



$10\bar{1}$ zone axis

AlGaN

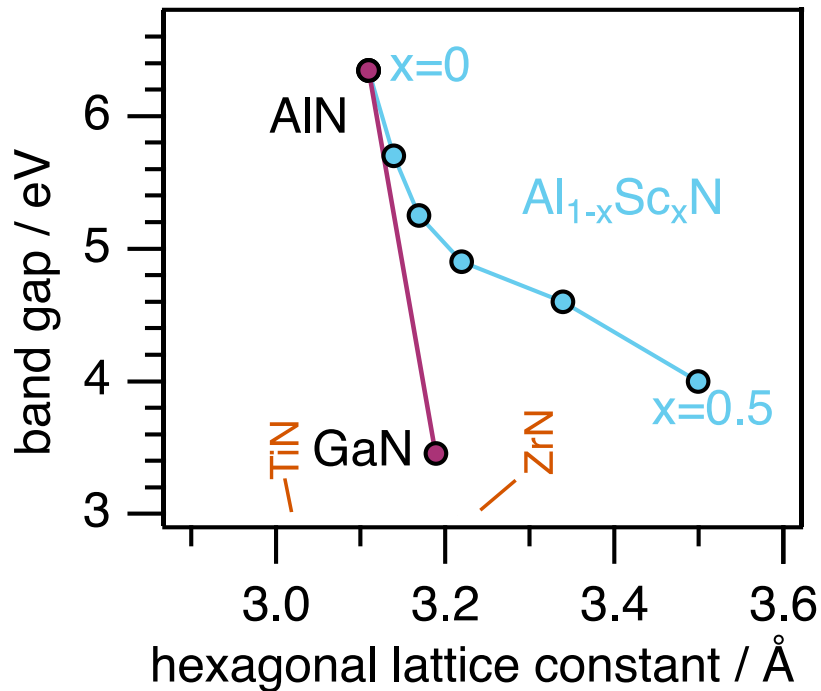


$11\bar{2}0$ zone axis

Substrates for other alloys

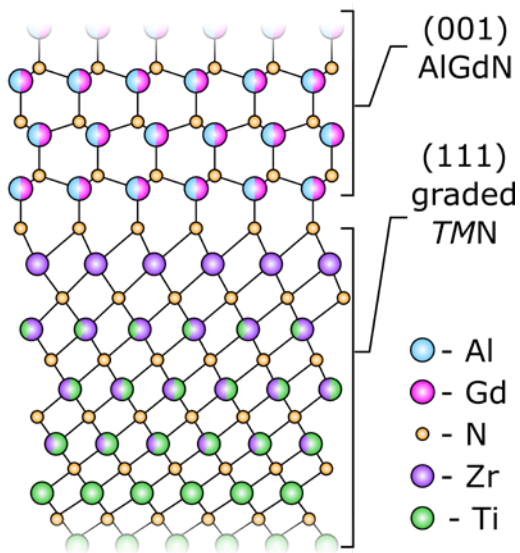
AlScN, AlGdN, etc

Virtual Substrates for Larger Lattice Constant Alloys



- Both carbides and nitrides are attractive for AlGaN, AlScN, and AlGdN alloys
- ZrN is appropriate for larger lattice constants but is difficult to stabilize – address with compositional grading

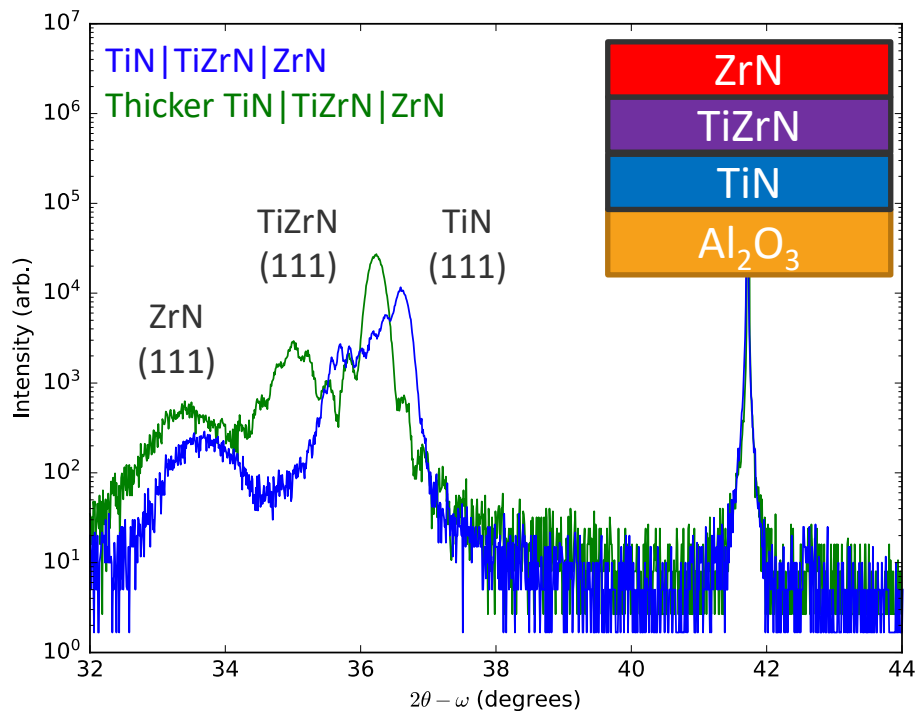
Virtual Substrates for Larger Lattice Constant Alloys



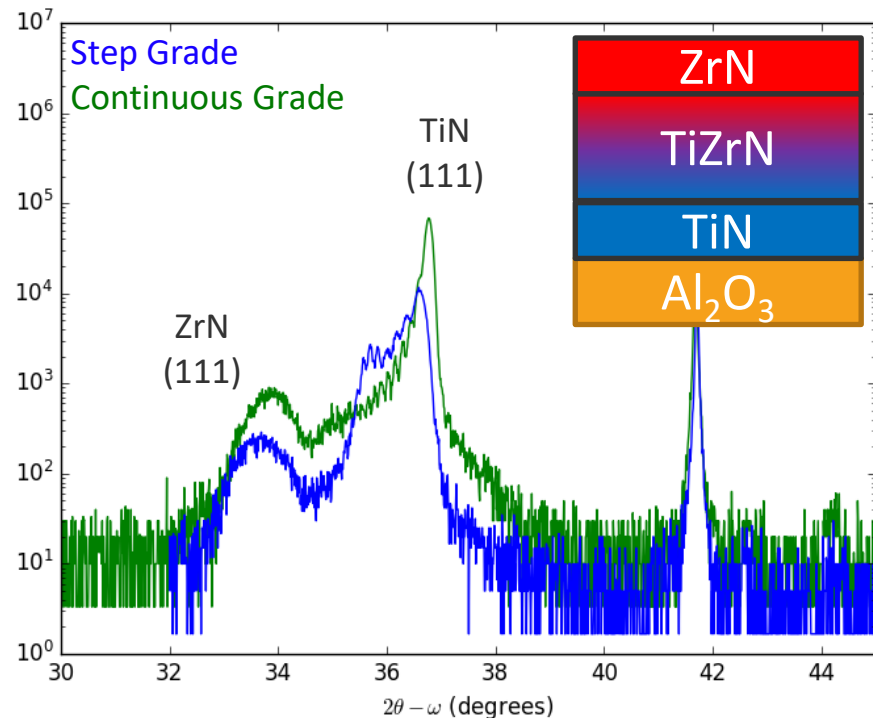
- Both carbides and nitrides are attractive for AlGa_xN_{1-x}, AlSc_xN_{1-x}, and AlGd_xN_{1-x} alloys
- ZrN is appropriate for larger lattice constants but is difficult to stabilize – address with compositional grading

Graded transition metal nitride buffers by RF Sputtering

Step Grade

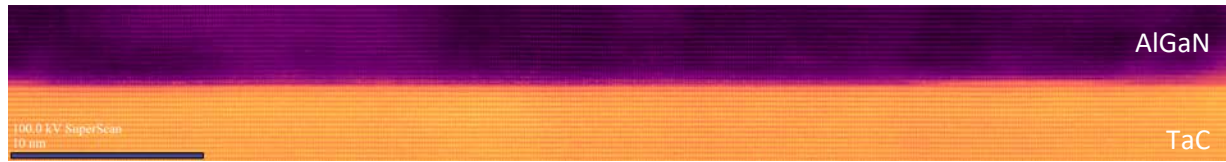
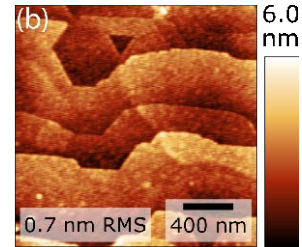
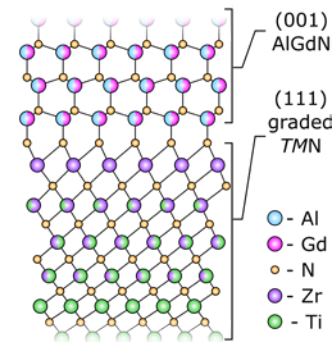
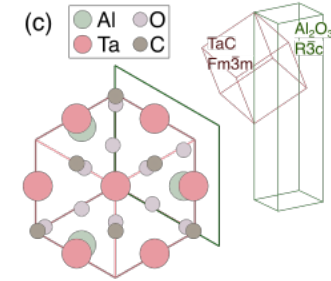


Continuous Grade



Conclusions – thin film virtual substrates can provide metallic lattice matching for Al-X-N

- TaC thin film virtual substrates were created by RF Sputtering
- Face-to-face annealing is effective at improving the crystallinity and surface morphology
- Rocksalt nitride compositional grades (step and continuous) have been demonstrated by RF Sputtering
- Proof of concept heteroepitaxy demonstrates the potential for low cost and scalable virtual substrates





Thank you!

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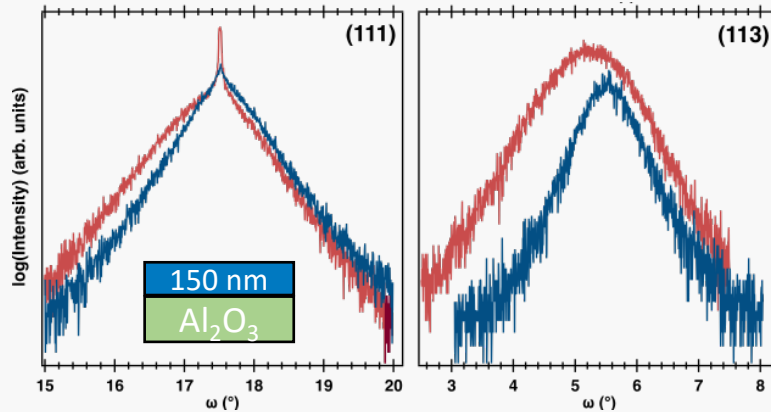
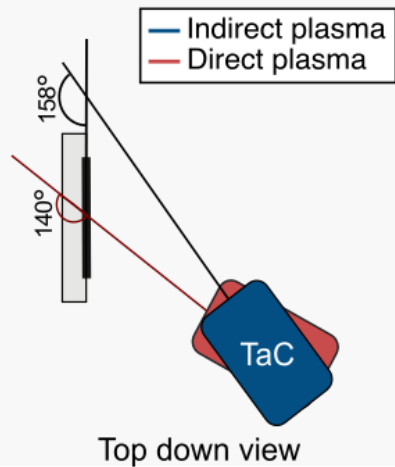
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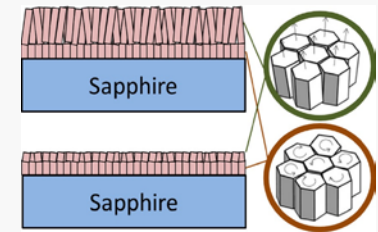
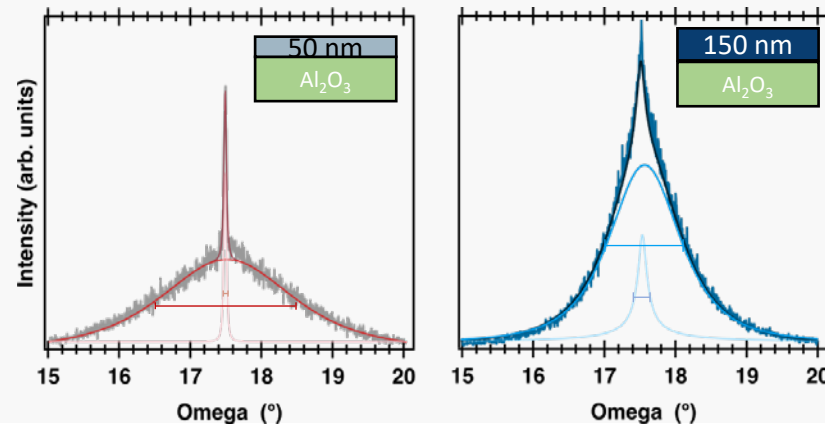
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Effects of thickness and incident angle

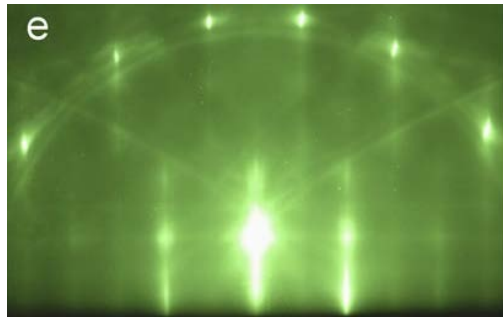
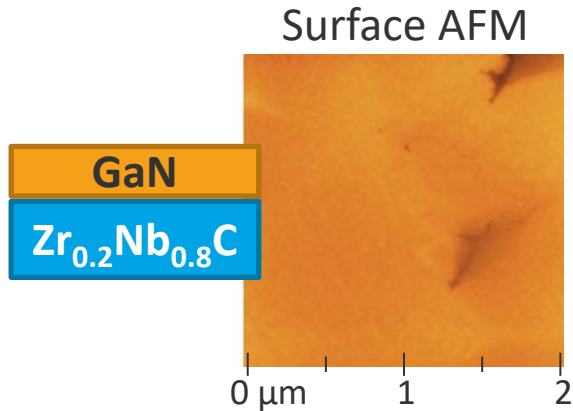


Fewer in-plane defects in indirectly sputtered film



AlN on Sapphire
Miyake et al, J. Cryst Growth 2016

Proposed solution



Aizawa et al, J Crys Growth 2008

Previous literature

Inspired by Amano *et al* GaN studies – growth on Zr_{0.2}Nb_{0.8}C

Proposed work

- Transition metal carbides and nitrides
 - TaC (111) is lattice matched to Al_{0.55}Ga_{0.45}N
 - Compatible coefficient of thermal expansions
- Potential tunability via alloying